1752



May 3, 2002

Commissioner of Patents and Trademarks Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572 20 McIntosh Drive Poughkeepsie, N.Y. 12603

Subject:

Serial No. 10/072,102 02/08/02

Chew Hoe Ang et al.

A METHOD TO PATTERN SMALL FEATURES BY USING A RE-FLOWABLE HARD MASK

Grp. Art Unit: 1752

RECEIVED
TC 1700

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231, on May 14, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

- 5/14/02

CS-01-027

- U.S. Patent 4,022,932 to Feng, "Resist Reflow Method for Making Submicron Patterned Resist Masks," describes a resist reflow method for making submicron patterned resist masks.
- U.S. Patent 5,899,746 to Mukai, "Method of Forming Pattern," describes a method for making small patterns by eroding a photoresist pattern.
- U.S. Patent 4,824,747 to Andrews, "Method of Forming a Variable Width Channel," describes a method for forming a variable width channel.
- U.S. Patent 4,449,287 to Maas et al., "Method of Providing a Narrow Groove or Slot in a Substrate Region, in Particular a Semiconductor Substrate Region," describes a method of providing a narrow groove or slot in a substrate region.
- U.S. Patent 4,546,066 to Field et al., "Method for Forming Narrow Images on Semiconductor Substrates," describes a method for forming narrow images on semiconductor substrates.

Sincerely,

Stephen B. Ackerman,

Reg. No. 37761